



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Application of:

GREGORY C. WEED ET AL

CASE NO.: IM0877 US CIP

SERIAL NO.: 09/775,988

GROUP ART UNIT: 1752

FILED: FEBRUARY 2, 2001

EXAMINER: CYNTHIA HAMILTON

FOR: NEAR IR SENSITIVE

PHOTOIMAGEABLE/PHOTOPOLYMERIZAB

LE COMPOSITIONS, MEDIA, AND

ASSOCIATED PROCESSES

AMENDMENT UNDER 37 C.F.R. §1.111

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Assistant Commissioner for Patents Washington, DC 20231

JAN 3 1 2003

Sir:

PETITIONS OFFICE

This amendment is being submitted together with a "Petition for Revival of an Application for Patent Abandoned Unintentionally Under 37 C.F.R. 1.137(b)".

In response to the Office Action dated JUNE 18, 2002, please amend the above-referenced application as follows:

IN THE SPECIFICATION:

Please make changes on page 12, line 21.

Preferably, R_e and R_f are hydrogen or alkyl of 1-4 carbon atoms. Leuco dye is present in 0.1 to 5.0 percent by weight of solids in the photoimaging composition.

Please make changes on page 32, line 21.

COMPARATIVE EXAMPLES In this comparative example, a photopolymer film was made and tested in the manner as given in Examples 27-29, except that SQS, a near IR dye photosensitizer that is very effective for thermal imaging (see U.S. Patent 5,019,549), was used in equimolar levels in place of the near IR dyes tested in Examples 27-29. All other procedures were the same as previously described. Upon exposure and during the course of development, all of the photopolymer film was washed off the copper surface leaving a nearly bare or bare copper substrate with no image. This experiment indicates that the combination of SQS and a HABI photoinitiator is not capable of efficiently initiating the polymerization of monomer(s) in a photopolymer film upon exposure to near IR actinic radiation, such that both exposed and unexposed areas remain unpolymerized and are thus washed off in the course of

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